

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re United States Patent Application of:	)	Docket No.:	020732-97.668	
	)		(7493)	
	)			
Applicants:	RATH, Melissa K., et al.	)	Conf. No.:	4823
		)		
Application No.:	10/792,038	)	Art Unit:	1752
		)		
Date Filed:	March 3, 2004	)	Examiner:	LE, Hoa Van
		)		
Title:	COMPOSITION AND PROCESS FOR POST-ETCH REMOVAL OF PHOTORESIST AND/OR SACRIFICIAL ANTI-REFLECTIVE MATERIAL DEPOSITED ON A SUBSTRATE	)	Customer No.:	<b>24239</b>
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**AMENDMENT RESPONDING TO FEBRUARY 24, 2009 OFFICE ACTION IN UNITED  
STATES PATENT APPLICATION NO. 10/792,038**

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Mail Stop Final  
Commissioner for Patents  
PO Box 1450  
Alexandria, VA 22313-1450

Sir:

This responds to the February 24, 2009 Office Action in the above-identified application.

Please amend the claims, as set out in the following **Section I (the Claims)**.

Remarks addressing the substance of the February 24, 2009 Office Action are set out in the **Section II (Remarks)** hereof.